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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Kouji Fujiyoshi et al.) Group Art Unit 2823
Appl. No. : 10/712,594)
Filed : November 12, 2003)
For : ELECTRON BEAM EXPOSURE)
APPARATUS, ELECTRON BEAM)
EXPOSING METHOD,)
SEMICONDUCTOR ELEMENT)
MANUFACTURING METHOD, AND)
PATTERN ERROR DETECTION)
METHOD)
Examiner : William D. Coleman)

AMENDMENT

Hon. Commissioner
of Patents and Trademarks
Alexandria, VA 22313-1450

Dear Sir:

This amendment is submitted in response to the office action mailed July 1, 2005 from the United States Patent and Trademark Office for the above-identified patent application. Please make the following changes: